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In the Claims

CLAIMS

Claims 1-30 (Canceled).

(Currently amended) An engagement probe formed from a semiconductor 31. material, and having comprising:

a substrate;

a projection supported over the substrate and comprising material of the substrate; and

a grouping of a plurality of projecting apexes extending from the projection and positioned is in sufficient proximity to one another to collectively engage a single conductive pad on a semiconductor substrate.

- (Previously presented) The engagement probe of claim 31 comprising a 32. plurality of such groupings for engaging multiple conductive pads on the semiconductor substrate.
- 33... (Previously presented) The engagement probe of claim 31 wherein the apexes are in the shape of multiple knife-edge lines.

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- (Previously presented) The engagement probe of claim 31 wherein the 34. apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines being positioned to form at least one polygon.
- (Previously presented) The engagement probe of claim 31 wherein the 35. apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines being positioned to form at least two polygons one of which is received entirely within the other.
- (Currently amended) The engagement probe of claim 31 wherein the 36. grouping of apexes is formed on a the projection which is supported by another projection. the another projection extending directly from a the substrate.
- 37. (Previously presented) The engagement probe of claim 31 wherein the apexes have a selected projecting distance, the projecting distance being about one-half the thickness of the conductive pad which the apparatus is adapted to engage.
- (Currently amended) The engagement probe of claim 31 wherein the apexes 38. project from a common plane of the projection, the apexes having respective tips and bases, the bases of adjacent projecting apexes being spaced from one another to define a penetration stop plane therebetween.

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- 39. (Currently amended) The engagement probe of claim 31 wherein the apexes project from a common plane of the projection, the apexes having respective tips and bases, the bases of adjacent projecting apexes being spaced from one another to define a penetration stop plane therebetween, the tips being a distance from the penetration stop plane of about one-half the thickness of the conductive pad which the apparatus is adapted to engage.
- 40. (Previously presented) The engagement probe of claim 31 wherein the apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines interconnecting to form at least one fully enclosed polygon.
- 41. (Previously presented) The engagement probe of claim 31 wherein outermost portions of the electrically conductive apexes constitute a first electrically conductive material, and wherein the conductive pads for which the probe is adapted have outermost portions constituting a second electrically conductive material; the first and second electrically conductive materials being different.
- 42. (New) An engagement probe formed from a semiconductor material and having a grouping of a plurality of projecting apexes positioned in sufficient proximity to one another to collectively engage a single conductive pad on a semiconductor substrate; and wherein the apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines being positioned to form at least one polygon.

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- 43. (New) An engagement probe formed from a semiconductor material and having a grouping of a plurality of projecting apexes positioned in sufficient proximity to one another to collectively engage a single conductive pad on a semiconductor substrate; and wherein the apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines being positioned to form at least two polygons one of which is received entirely within the other.
- 44. (New) An engagement probe formed from a semiconductor material and having a grouping of a plurality of projecting apexes positioned in sufficient proximity to one another to collectively engage a single conductive pad on a semiconductor substrate; and wherein the apexes are in the shape of multiple knife-edge lines, the multiple knife-edge lines interconnecting to form at least one fully enclosed polygon.
- 45. (New) The engagement probe of claim 31 wherein the plurality of the projecting apexes extend from a substantially planar uppermost surface of the projection.
- 46. (New) The engagement probe of claim 31 wherein an entirety of the projection is spaced from the substrate.
- 47. (New) The engagement probe of claim 31 wherein the substrate comprises bulk silicon.

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48. (New) The engagement probe of claim 31 wherein the projection comprises a lateral dimension less than a lateral dimension of the substrate.